

Substitute for form 1449A/PTO & 1449B/PTO		Complete if Known	
FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/764,407
		Filing Date	January 23, 2004
		First Named Inventor	Shenggao Liu et al.
		Examiner Name	
Sheet 1 of 1	3	Attorney Docket Number	005950-844

U.S. PATENT DOCUMENTS				
Examiner Initials	Document Number	Kind Code (if known)	Name of Patentee or Applicant of Cited Document	Issue/Publication Date (MM-DD-YYYY)
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Examiner Signature	Date Considered	9-8-05
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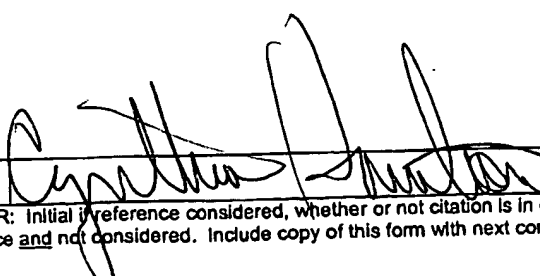
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					Translation	Partial Translation	Eng. Lang. Summary	Search Report	IPER	Abstract	Cited in Spec
CH CH CH	WO 92/13909		PCT	08/20/92							
	WO 02/058139		PCT	07/25/02							
	WO 02/088077		PCT	11/07/02							

NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
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